## FORMATION OF ULTRATHIN CdS-FILMS ON CU(111) – AN IN-SITU STM STUDY

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Electrochemical Atomic Layer Epitaxy (ECALE) has been found to be a useful method to grow thin layers of semiconductor compounds at solid/liquid interfaces [1].

In this contribution we present STM data dealing with the epitaxial growth of ultrathin CdS-films on a Cu(111) electrode surface.

It will be shown that the atomic structure and the morphology of the resulting 2 layers thick CdS film strongly depend on the first layer adsorbed on the copper substrate.

A first preparation method of the CdS-films started with a sulfide covered copper surface.

Depending on the applied electrode potential two different sulfide layers can be observed by STM as reported by Wan et al. [2], on top of a Cu(111) surface exposed to a 10 mM S<sup>2-</sup> electrolyte:

1. an incommensurate moiré pattern (Fig. 1)

2. a commensurate  $(\sqrt{7}X\sqrt{7})R19.1^{\circ}$ -adlayer (Fig.2) There is a broad potential regime in which both phases coexist. A deposition of the Cd within this sulfide coexistence regime does affect only the commensurate

 $(\sqrt{7}X\sqrt{7})R19.1^{\circ}$  phase, while the incommensurate moiré pattern remains unaffected.

Cd deposition on the  $(\sqrt{7}X\sqrt{7})R19.1^{\circ}$  phase at a potential of -375 mV with respect to the RHE results in the formation of a CdS-phase revealing a complex dislocation network.

A totally different CdS phase can be observed starting with a Cd-UPD layer on top of the copper surface which is subsequently modified by a sulfide adsorption process.

References:

[1] T.E. Lister, J.L.Stickney, Applied Surface Science 107 (1996) 153-160

[2] Wang D. Xu Qm, Wan et al., Surf. Science, 499 L 159-163



Fig. 1: Incommensurate S<sup>2-</sup> induced moiré pattern on Cu(111) 12.78 nm x 12.78 nm



Fig. 2: Commensurate  $(\sqrt{7}X\sqrt{7})R19.1^{\circ}S^{2}$ -adlayer on Cu(111) 15.1 nm x 15.1 nm



Fig. 3: Dislocation network seen for a S2-/Cd coadsoption layer on Cu(111) 27.1 nm x 27.1 nm